

METHOD AND DEVICE FOR EXPOSURE

Publication Number: 2003-234285 (JP 2003234285 A) , August 22, 2003

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Application Number: 2002-123268 (JP 2002123268) , April 24, 2002

Priority:

- 2001-369393 [JP 2001369393], JP (Japan), December 03, 2001
- 2001-126759 [JP 2001126759], JP (Japan), April 24, 2001

International Class:

- H01L-021/027
- G03F-001/08
- G03F-007/20

Abstract:

PROBLEM TO BE SOLVED: To provides method and device for exposure capable of exposing a pattern, having a fine hole diameter and patterns of rows of contact holes or mixed independent contact holes with the rows of contact holes, with a high degree of resolution (or the degree of resolution equal to L-and-S pattern employing a phase shift mask for the rows of contact holes) without exchanging any mask. **SOLUTION:** The mask is projected against a body to be exposed through a projection optical system by a method wherein the mask, on which the patterns of contact holes and another pattern having a size smaller than that of the pattern of the contact hole are arrayed, is irradiated by a plurality of kinds of light so that the patterns of the contact holes are resolved and the resolution of the pattern having the small size is restrained. **COPYRIGHT:** (C)2003,JPO

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Dialog® File Number 347 Accession Number 7740383